

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re United States Patent Application of:)	Docket No.:	020732-97.668
)		(7493)
Applicants:)	Conf. No.:	4823
RATH, Melissa K., et al.)		
Application No.:)	Art Unit:	1752
10/792,038)		
Date Filed:)	Examiner:	LE, Hoa Van
March 3, 2004)		
Title:)	Customer No.:	24239
COMPOSITION AND PROCESS FOR)		
POST-ETCH REMOVAL OF)		
PHOTORESIST AND/OR)		
SACRIFICIAL ANTI-REFLECTIVE)		
MATERIAL DEPOSITED ON A)		
SUBSTRATE)		

**RESPONSE TO APRIL 13, 2006 OFFICE ACTION; SUBMISSION OF DECLARATION
UNDER 37 CFR §1.131; AND REQUEST FOR A TWO-MONTH EXTENSION UNDER
37 CFR §1.136(a) IN UNITED STATES PATENT APPLICATION NO. 10/792,038**

Mail Stop Amendment
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

Please amend the claims, as set out in the following **Section I (the Claims)**.

Remarks addressing the substance of the April 13, 2006 Office Action are set out in the **Section II (Remarks)** hereof.

A Declaration under 37 CFR §1.131 is included herewith in **Appendix A**.